

(Use several sheets if necessary)

SERIAL NO.
PCT/JP00/06038

09/830598

September 6, 2000

JC18 Rec'd CRUPTO 27 APR 2001
2000 1756

[illegible]

		DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION	
							YES	NO
10		40-78647	03-1998	JAPAN				✓
7		219204	08-1995	JAPAN				✓
7		168343	07-1995	JAPAN				✓
6		282063	10-1994	JAPAN				✓
5		175346	06-1994	JAPAN				✓

DATE CONSIDERED

*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

INFORMATION DISCLOSURE STATEMENT
(Use several sheets if necessary)

Docket Number (Optional)

A-398

Application Number

09/830,598 (PCT/JP00/06038)

Applicant(s)

Junji FUJIKAWA et al

Filing Date

April 27, 2001 (Feb. 5, 2003)

Group Art Unit

1756

U.S. PATENT DOCUMENTS

*EXAMINER INITIAL	REF	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
JS		5,482,799	01-1996	Isao et al	430	5	
JS		5,721,075	02-1998	Hashimoto et al	430		

FOREIGN PATENT DOCUMENTS

REF	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	Translation	
						YES	NO

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)

SMITH B W ET AL: "ATTENUATED PHASE SHIFT MASK MATERIALS FOR 248- AND 193-NM LITHOGRAPHY"
MICROLITHOGRAPHY WORLD, PENNWEILL PUBLISHING COMPAGNY, US, vol. 6, no. 2, 21 March 1997
(1997-03-21), pages 7-8, 10, 12, 19, XP000688905 ISSN: 1074-0407

EXAMINER

J. D. [Signature]

DATE CONSIDERED

4/25/03

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